

Supporting Information

Molecular orientation of terephthalic acid assembly on epitaxial graphene: NEXAFS and XPS study

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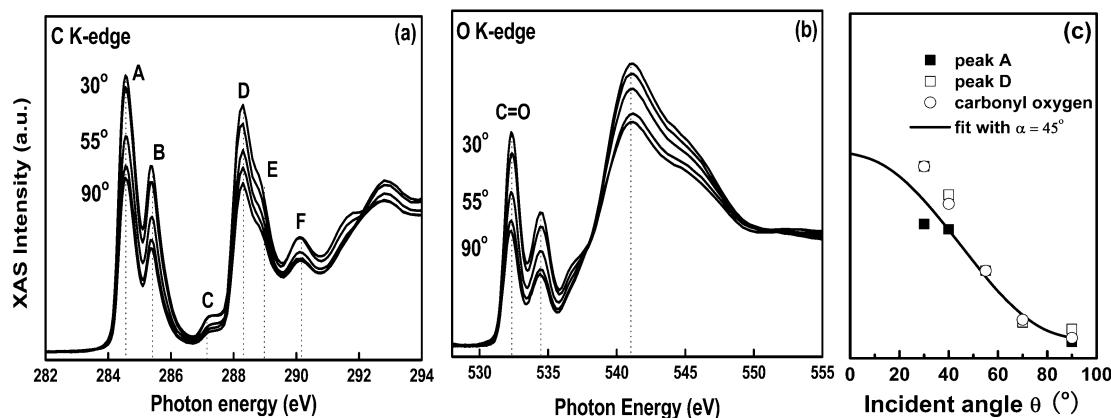


Figure SI1. NEXAFS spectra of TPA multilayer on EG/Ni(111) measured at series of incident angles θ : 30°, 40°, 55°, 70°, 90°: (a) C K-edge; (b) O K-edge; (c) The fitting of the incident angle dependence of peak A (filled squares), peak D (open squares) and oxygen carbonyl peak (open circles) with $\alpha = 45^\circ$.